

Supporting Information:

**Two-dimensional Ferroelectric MoS₂/Ga₂O₃
Heterogeneous Bilayers with Highly Tunable
Photocatalytic and Electrical Properties**

Haohao Chen^{∇,†}, Junlei Zhao^{∇,†}, Xinyu Wang,[†] Xiaolong Chen,[†] Zhaofu
Zhang,^{*,‡} and Mengyuan Hua^{*,†}

*†Department of Electrical and Electronic Engineering, Southern University of Science and
Technology, Shenzhen 518055, China*

*‡Department of Engineering, University of Cambridge, Cambridge CB2 1PZ, United
Kingdom*

E-mail: zz389@cam.ac.uk; huamy@sustech.edu.cn

Extended Computational data

Searching of Stable Stacking Configurations

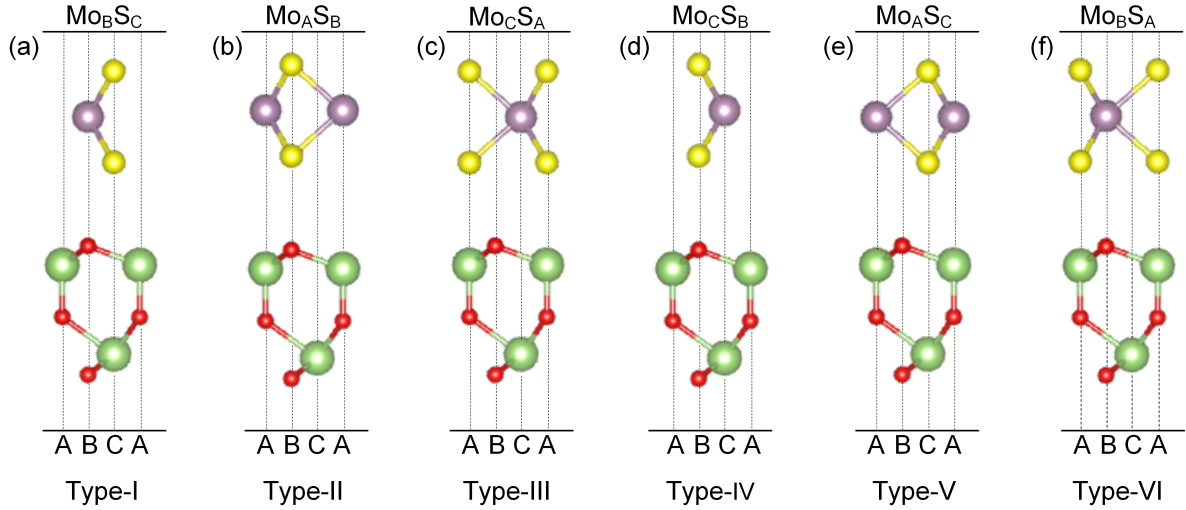


Fig. S1 Schematic views of relaxed $\text{MoS}_2/\text{Ga}_2\text{O}_3\uparrow$ heterostructures with various high-symmetry atomic arrangements. (a) to (f) are labeled as Type-I to Type-VI, respectively.

Table S1: Energy difference of $\text{MoS}_2/\text{Ga}_2\text{O}_3\uparrow$

Heterostructure	Energy Difference (meV per unit cell)
Type-I	6.55
Type-II	61.07
Type-III	0
Type-IV	60.44
Type-V	5.93
Type-VI	2.78

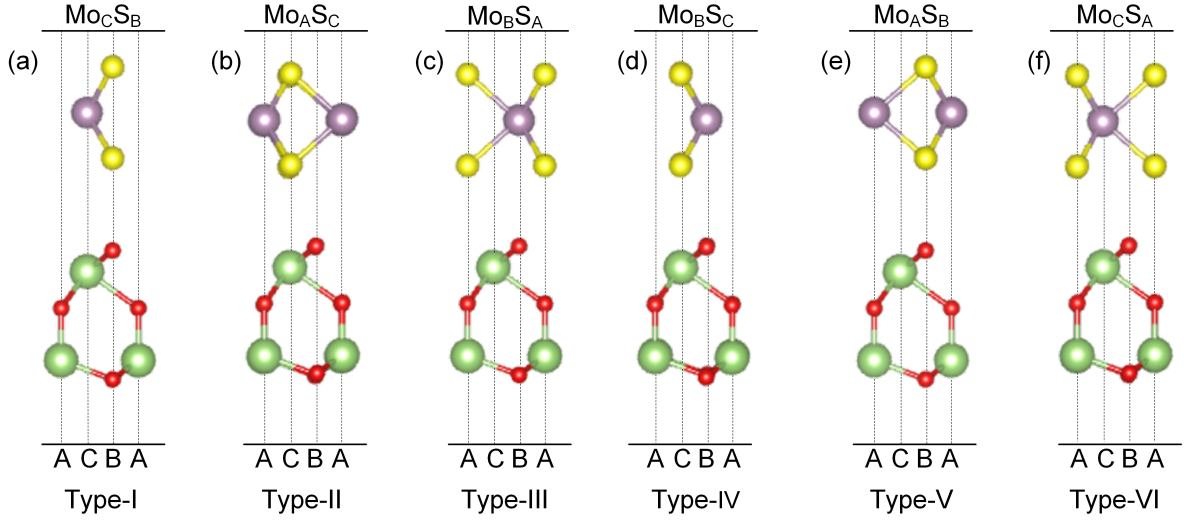


Fig. S2 Schematic views of relaxed $\text{MoS}_2/\text{Ga}_2\text{O}_3\downarrow$ heterostructures with various high-symmetry atomic arrangements. (a) to (f) are labeled as Type-I to Type-VI, respectively.

Table S2: Energy difference of $\text{MoS}_2/\text{Ga}_2\text{O}_3\downarrow$

Heterostructure	Energy Difference (meV per unit cell)
Type-I	64.27
Type-II	1.81
Type-III	4.04
Type-IV	5.39
Type-V	64.20
Type-VI	0

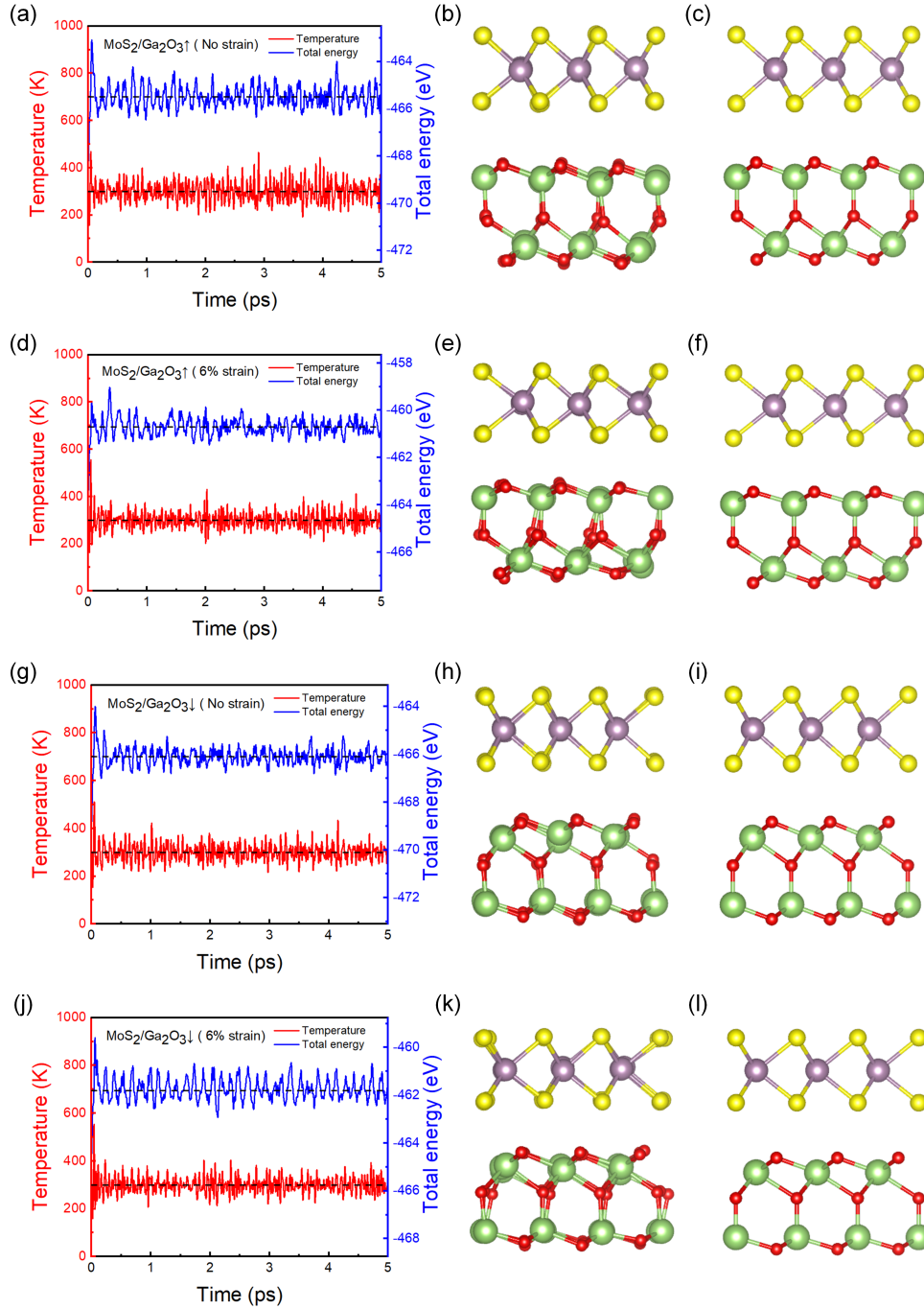


Fig. S3 Evolution of temperature (red, left axis) and total energy (blue, right axis) with time during AIMD simulations for (a, d) MoS₂/Ga₂O₃↑ and (g, j) MoS₂/Ga₂O₃↓ heterostructures under relaxed station and 6% tensile strain, respectively. Atomic structures of the heterostructures after (b,e,h,k) 5 ps AIMD simulations at 300 K and further (c,f,i,l) geometry relaxations, respectively.

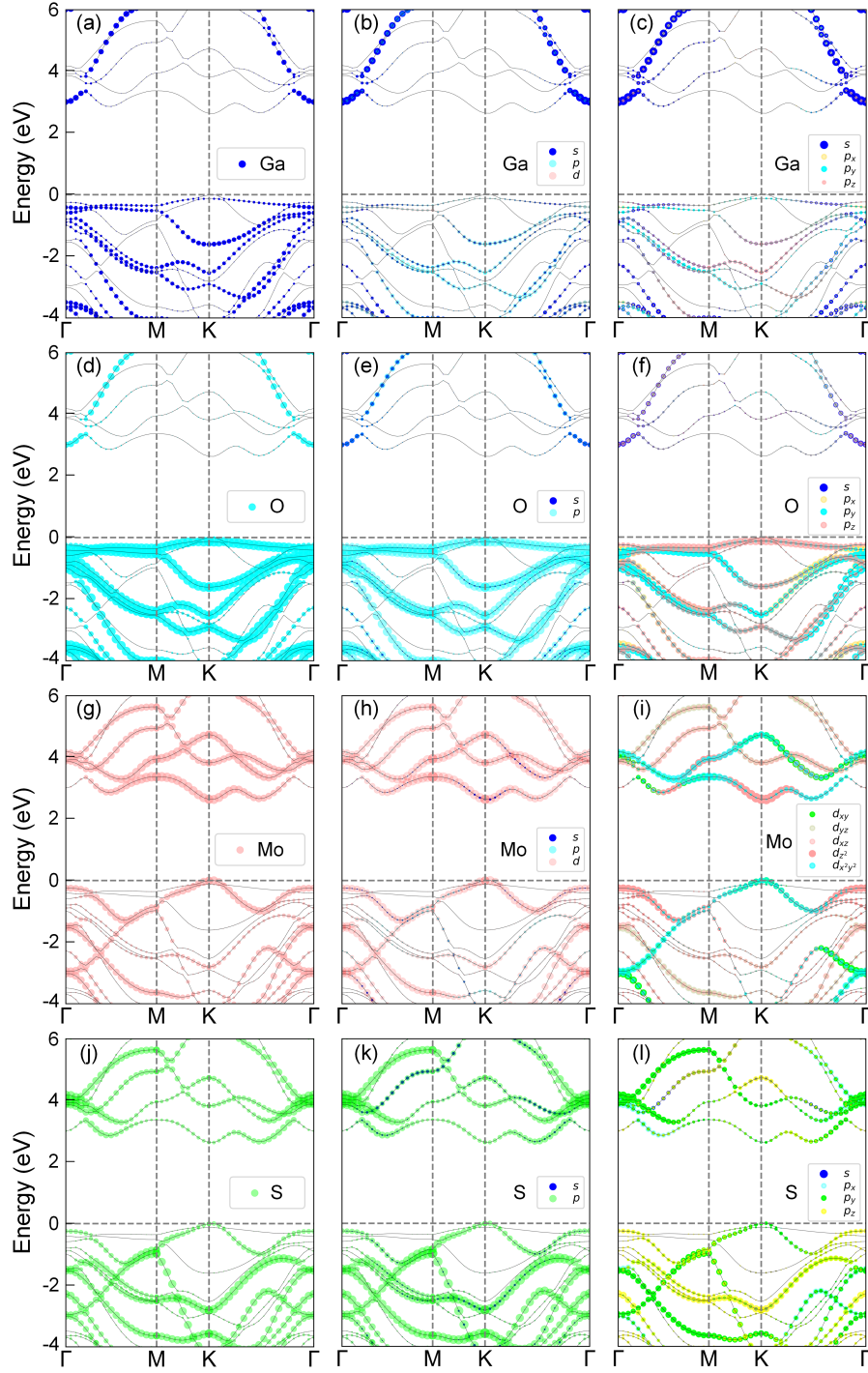


Fig. S4 Projected band structure of $\text{MoS}_2/\text{Ga}_2\text{O}_3\uparrow$ heterostructure for orbitals of (a) Ga (b) Ga- s , Ga- p , Ga- d (c) Ga- s , Ga- p_x , Ga- p_y , Ga- p_z (d) O (e) O- s , O- p (f) O- s , O- p_x , O- p_y , O- p_z (g) Mo (h) Mo- s , Mo- p , Mo- d (i) Mo- d_{xy} , Mo- d_{yz} , Mo- d_{xz} , Mo- d_{z^2} , Mo- $d_{x^2-y^2}$ (j) S (k) S- s , S- p (l) S- s , S- p_x , S- p_y , S- p_z , respectively.

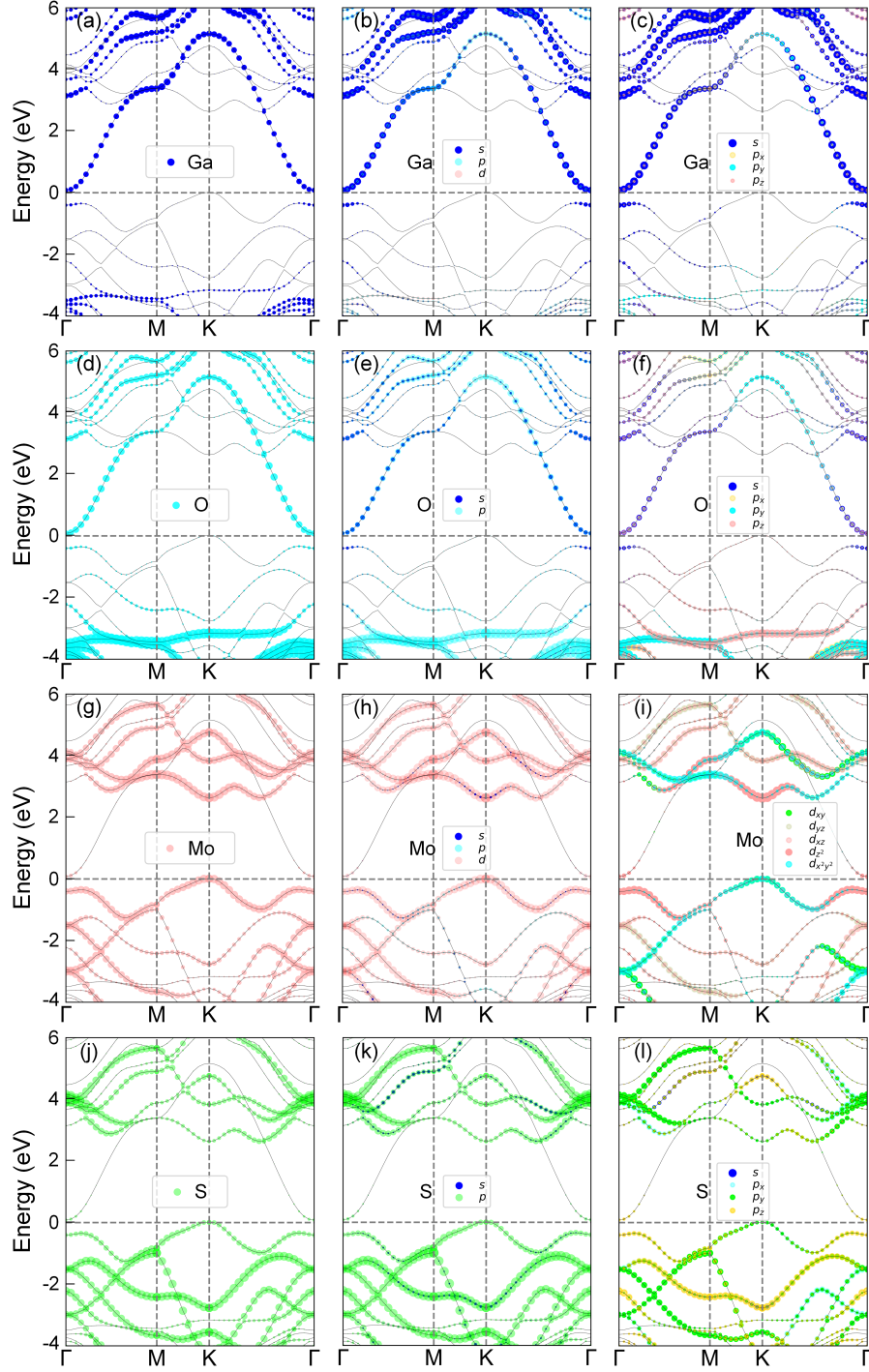


Fig. S5 Projected band structure of $\text{MoS}_2/\text{Ga}_2\text{O}_3\downarrow$ heterostructure for orbitals of (a) Ga (b) Ga- s , Ga- p , Ga- d (c) Ga- s , Ga- p_x , Ga- p_y , Ga- p_z (d) O (e) O- s , O- p (f) O- s , O- p_x , O- p_y , O- p_z (g) Mo (h) Mo- s , Mo- p , Mo- d (i) Mo- d_{xy} , Mo- d_{yz} , Mo- d_{xz} , Mo- d_{z^2} , Mo- $d_{x^2-y^2}$ (j) S (k) S- s , S- p (l) S- s , S- p_x , S- p_y , S- p_z , respectively.

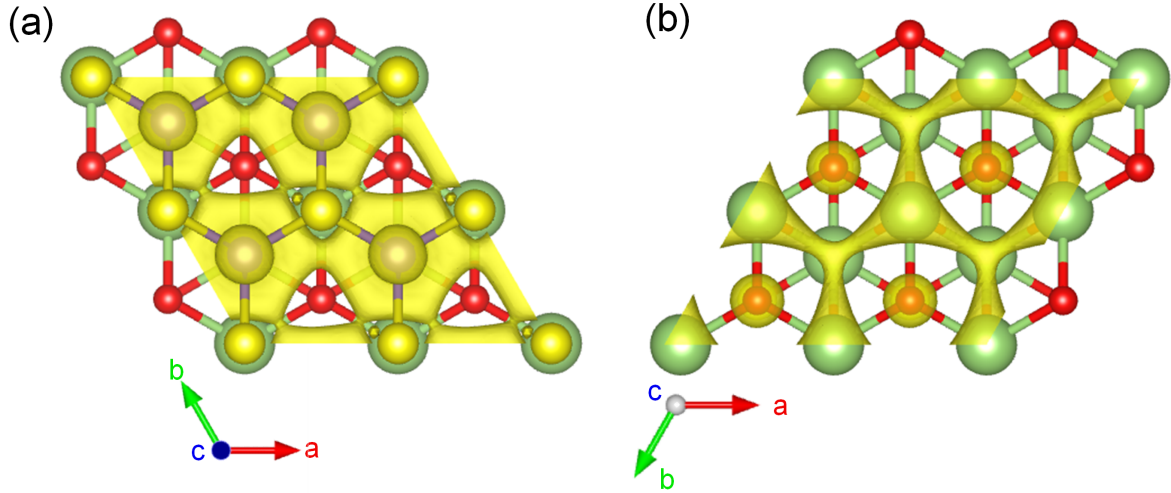


Fig. S6 Partial real-space probability distribution at CBM of (a) $\text{MoS}_2/\text{Ga}_2\text{O}_3\uparrow$ and (b) $\text{MoS}_2/\text{Ga}_2\text{O}_3\downarrow$, with the same isosurface level at $3.21 \times 10^{-8} e/\text{Bohr}^3$.

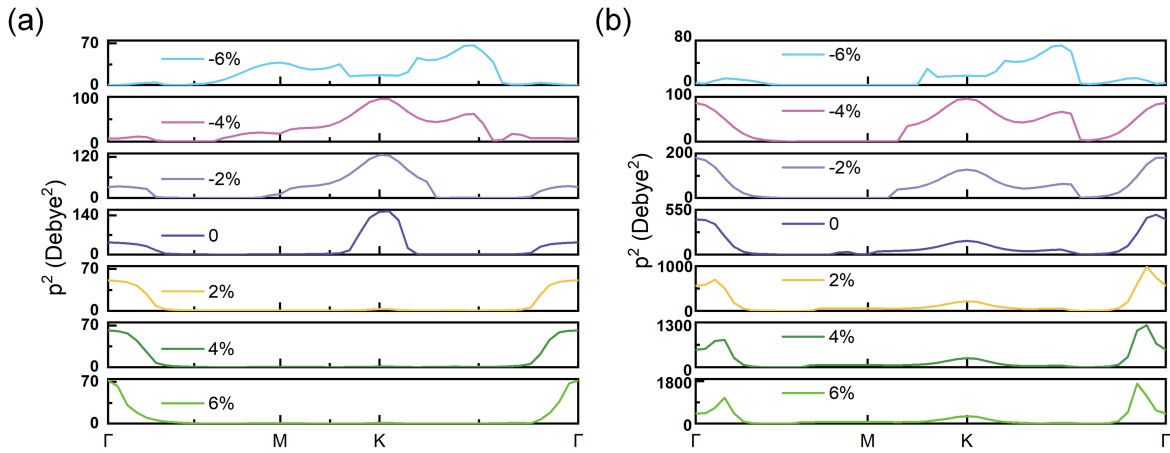


Fig. S7 Transition dipole moment of (a) $\text{MoS}_2/\text{Ga}_2\text{O}_3\uparrow$ and (b) $\text{MoS}_2/\text{Ga}_2\text{O}_3\downarrow$ versus biaxial strains.

The squared transition dipole moment (P^2) between the highest valence band and the lowest conduction band can be used to represent the transition probability of electrons,^{S1,S2} as shown in Fig. S7a,b.

For $\text{MoS}_2/\text{Ga}_2\text{O}_3\uparrow$, with decreasing compressive strain and increasing tensile strain, the transition probability of electrons tends to increase in the Γ point region. In the high-symmetry K point region, the electron transition probability under tensile strain is much

smaller than that of compressive strain. This is because under tensile strain conditions, the conduction band is derived from MoS₂, while the valance band is occupied by Ga₂O₃. The electronic transition not only overcomes the band gap but also considers the effect of interlayer transition and intrinsic dipole moment on electrons. It is obvious that P^2 of MoS₂/Ga₂O₃↓ is much higher than MoS₂/Ga₂O₃↑. What's more, under the tensile strain of 6%, the electron transition with three-times enhancement in MoS₂/Ga₂O₃↓ is observed due to gap narrowing near the Γ region. As a result, the high P^2 and good light absorption show advantages and potentials in solar energy conversion such as photocatalytic water splitting and photodetection.

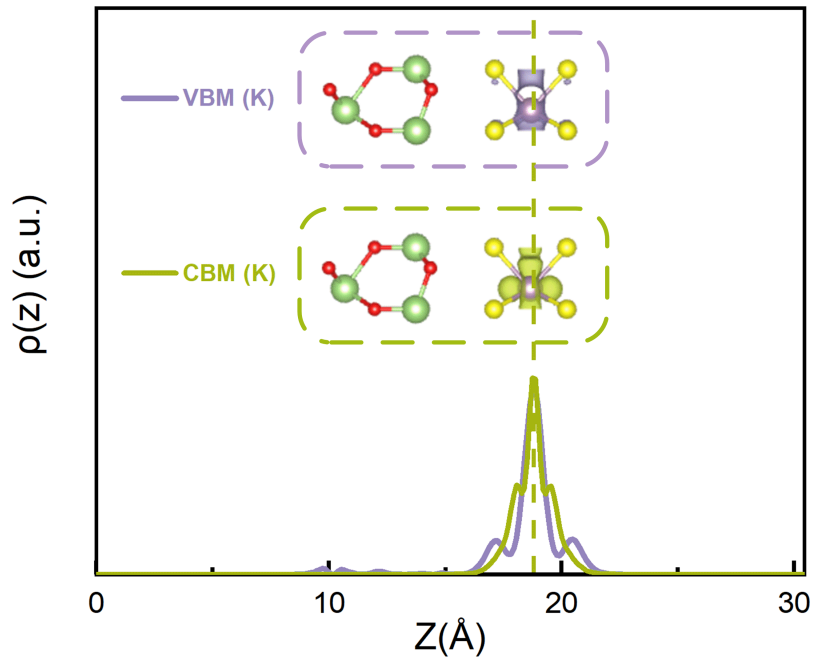


Fig. S8 The real-space probability distribution of MoS₂/Ga₂O₃↑ heterostructure along the z direction. The insets show its real-space probability distribution of VBM (K) and CBM (K), respectively, with the same isosurface level at $3.21 \times 10^{-8} e/\text{Bohr}^3$.

References

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- (S2) Liao, Y.; Zhang, Z.; Gao, Z.; Qian, Q.; Hua, M. Tunable properties of novel Ga₂O₃ monolayer for electronic and optoelectronic applications. *ACS Appl. Mater. Interfaces* **2020**, *12*, 30659–30669.